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反应磁控溅射制备Ti-Si-N薄膜的摩擦磨损性能

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摘要: 用反应磁控溅射方法, 在不锈钢表面沉积Ti-Si-N薄膜。用原子力显微镜观察薄膜的表面形貌, Ti-Si-N颗粒尺寸小于0.1 μ m, 用亚微压入仪测试薄膜硬度, 当硅的摩尔分数为9.6%时, 薄膜硬度出现最大值47GPa。球-盘式摩擦磨损结果表明, Ti-Si-N薄膜的耐磨性能明显优于TiN薄膜, 加入少量硅元素后, TiN薄膜的抗磨损性能有显著提高, 但Ti-Si-N薄膜的室温摩擦系数较高(0.6-0.8), 高温下摩擦系数也仅轻微降低(550 $^{\circ}$ C, 0.5-0.6)。由于Ti-Si-N薄膜的摩擦系数可能与磨损中氧化物生成量的增加有关, 常温下Ti-Si-N薄膜的摩擦系数随硅摩尔分数的增加而增大, 而高温下Ti-Si-N薄膜的摩擦系数随硅含量上升而降低。

关键词: Ti-Si-N薄膜; 反应磁控溅射; 摩擦学

Tribological behavior of Ti-Si-N coatings prepared by magnetron sputtering reactive deposition

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Abstract: Multiphase nanocomposite thin films composed of nanocrystalline TiN and nano-sized amorphous Si₃N₄ were deposited on stainless steel substrate at 550 $^{\circ}$ C using magnetron sputtering reactive deposition technique. The micro-hardness of Ti-Si-N films can reach 47GPa when molar fraction of silicon is 9.6%. Sliding friction and wear investigations were performed using ball-on-disk typed high-temperature tribometer without lubrication. The wear resistant properties of TiN film increase remarkably with certain addition of silicon, while friction coefficient remains high (about 0.6~0.8) at room temperature and reduces only slightly at elevated temperature (0.5~0.6 at 550 $^{\circ}$ C). The friction coefficient increases with increasing molar fraction of silicon at room temperature, but it will decrease with increasing molar fraction of silicon at elevated temperature, because the friction coefficient may relate to the increasing of oxides formations during wear test.

Key words: Ti-Si-N coating; reactive magnetron sputtering; tribological behavior

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